

EAST Search History

EAST Search History (Prior Art)

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|--------|--|-------------------------------------|------------------|---------|---------------------|
| S1 | 309701 | (siN or silicon nitride or "si.sub.3n.sub.4") | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2009/02/25 10:21 |
| S2 | 2445 | S1 and (siN or silicon nitride or "si.sub.3n.sub.4") same (multi-layer or layer) and ("n.sub.2" or nitrogen) with dens\$6 | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2009/02/25 10:21 |
| S3 | 448 | S1 and (siN or silicon nitride or "si.sub.3n.sub.4") same (multi-layer or layer) same ("n.sub.2" or nitrogen) with dens\$6 | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2009/02/25 10:23 |
| S4 | 0 | S3 and (siN or silicon nitride or "si.sub.3n.sub.4") same (multi-layer) same ("n.sub.2" or nitrogen) with dens\$6 | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2009/02/25 10:43 |
| S6 | 448 | S1 and (siN or silicon nitride or "si.sub.3n.sub.4") same (multi-layer or layer) same ("n.sub.2" or nitrogen) with dens\$6 | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2009/02/25 10:50 |
| S7 | 4 | S6 and (siN or silicon nitride or "si.sub.3n.sub.4") same (multi-layer) same ("n.sub.2" or nitrogen) with dens\$6 | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2009/02/25 10:50 |
| S8 | 4 | S6 and (siN or silicon nitride or "si.sub.3n.sub.4") with (multi-layer) same ("n.sub.2" or nitrogen) | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2009/02/25 10:50 |
| S28 | 7 | ("2004/0121085").URPN. | USPAT | ADJ | ON | 2009/02/25 14:10 |
| S29 | 309701 | (siN or silicon nitride or "si.sub.3n.sub.4") | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2009/02/25 14:16 |
| S30 | 732 | S29 and (hot wire or hotwire) | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2009/02/25 14:16 |
| S31 | 257 | S30 and (hydrogen or "h.sub.2") | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2009/02/25 14:18 |

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| S36 | 310022 | (siN or silicon nitride or "si.sub.3n.sub.4") | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2009/02/26 08:17 |
| S37 | 254 | S36 and (siN or silicon nitride or "si.sub.3n.sub.4") same treat\$4 same repeat \$4 | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2009/02/26 08:17 |
| S38 | 84 | S37 and (siN or silicon nitride or "si.sub.3n.sub.4") same treat\$4 with repeat\$4 | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2009/02/26 08:17 |
| S40 | 328874 | (siN or silicon nitride or "si.sub.3n.sub.4") | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2009/09/10 09:18 |
| S41 | 516 | S40 and (siN or silicon nitride or "si.sub.3n.sub.4") same (mult-layer or layer) same ("n.sub.2" or nitrogen) with dens\$6 | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2009/09/10 09:18 |
| S72 | 2 | "20040121085" | US-PGPUB; USPAT | ADJ | ON | 2010/01/17 09:47 |
| S88 | 1 | "6689220".pn. | US-PGPUB; USPAT; EPO | ADJ | ON | 2010/08/17 09:11 |
| S91 | 8588 | (siN or silicon nitride or "si.sub.3n.sub.4") and ((rectang\$7 with (puls\$4 or flow)) or simultaneous\$4 with (valve or switch\$4)) | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2010/08/17 10:04 |
| S92 | 1964 | S91 and ("h.sub.2" or hydrogen) | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2010/08/17 10:06 |
| S93 | 623 | S91 and ("h.sub.2" or hydrogen) with (treat\$6 or post-treat\$6 or posttreat\$6 or SiN or silicon nitride or "si.sub.3.n.sub.4") | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2010/08/17 10:07 |
| S94 | 97 | S91 and ("h.sub.2" or hydrogen) with (treat\$6 or post-treat\$6 or posttreat\$6 or SiN or silicon nitride or "si.sub.3.n.sub.4") same (dens\$6 or multi-layer or multiple layer) | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2010/08/17 10:07 |
| S95 | 92 | S94 and ("427"/\$.ccls. or CVD or vapor deposition) | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2010/08/17 10:08 |
| S96 | 10 | S91 and ("h.sub.2" or hydrogen) with (treat\$6 or post-treat\$6 or posttreat \$6) same (SiN or silicon nitride or "si.sub.3.n.sub.4") same (dens\$6 or multi-layer or multiple layer) | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2010/08/17 10:09 |

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| S97 | 141 | S91 and ("h.sub.2" or hydrogen) with (treat\$6 or post-treat\$6 or posttreat\$6) same (SiN or silicon nitride or "si.sub.3.n.sub.4") | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2010/08/17 10:10 |
| S98 | 164 | S91 and ("h.sub.2" or hydrogen) with (treat\$6 or post-treat\$6 or posttreat\$6 or dens\$6) same (SiN or silicon nitride or "si.sub.3.n.sub.4") | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2010/08/17 10:10 |
| S99 | 4 | ((MAKIKO) near2 (KITAZOE)).INV. | US-PGPUB; USPAT | ADJ | ON | 2011/03/30 10:30 |
| S100 | 1 | ((HIROMI) near2 (ITHO)).INV. | US-PGPUB; USPAT | ADJ | ON | 2011/03/30 10:30 |
| S101 | 8 | ((SHIN) near2 (ASARI)).INV. | US-PGPUB; USPAT | ADJ | ON | 2011/03/30 10:30 |
| S102 | 44 | ((KAZUYA) near2 (SAITO)).INV. | US-PGPUB; USPAT | ADJ | ON | 2011/03/30 10:30 |
| S103 | 50 | S99 or S100 or S101 or S102 | US-PGPUB; USPAT | ADJ | ON | 2011/03/30 10:30 |
| S104 | 50 | S103 | US-PGPUB; USPAT | ADJ | ON | 2011/03/30 10:30 |
| S105 | 385382 | (siN or silicon nitride or "si.sub.3n.sub.4") | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2011/03/30 10:30 |
| S106 | 125 | S105 and (siN or silicon nitride or "si.sub.3n.sub.4") same (multi-layer or multiple layer) and ("n.sub.2" or nitrogen) with dens\$6 | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 10:30 |
| S107 | 173 | S105 and (siN or silicon nitride or "si.sub.3n.sub.4") same (multi-layer or multiple layer) and ("n.sub.2" or nitrogen or nh3 or "nh.sub.3" or ammonia) with dens\$6 | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 10:30 |
| S108 | 32 | S107 and (cat-cvd or catalyst) | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 10:31 |
| S109 | 3360 | S105 and (siN or silicon nitride or "si.sub.3n.sub.4") same (multi-layer or multiple layer) and ("n.sub.2" or nitrogen or nh3 or "nh.sub.3" or ammonia) | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 10:33 |
| S110 | 402 | S109 and (cat-cvd or catalyst) | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 10:33 |

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|------|--------|--|-------------------------------------|-----|----|---------------------|
| S111 | 1 | "20020104477" | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 10:36 |
| S112 | 27 | S110 and "427"/\$.ccls. | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 10:38 |
| S113 | 2 | "20040121085" | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 10:38 |
| S114 | 1 | "20010012650" | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 10:41 |
| S115 | 1 | "6017784".pn. | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 10:43 |
| S116 | 1045 | S109 and (cat-cvd or catalyst or wire or hotwire) | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 10:44 |
| S117 | 41 | S116 and "427"/\$.ccls. | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 10:45 |
| S118 | 385382 | (siN or silicon nitride or "si.sub.3n.sub.4") | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2011/03/30 12:07 |
| S119 | 2424 | S118 and (siN or silicon nitride or "si.sub.3n.sub.4") same (multi-layer or multiple layer) and ("h.sub.2" or hydrogen) | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 12:07 |
| S121 | 796 | S119 and (cat-cvd or catalyst or wire or hotwire) | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 12:08 |
| S122 | 797 | S118 and (siN or silicon nitride or "si.sub.3n.sub.4") same (multi-layer or multiple layer) and ("h.sub.2" or hydrogen) same (siN or silicon nitride or "si.sub.3n.sub.4") | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 12:08 |
| S123 | 199 | S122 and (cat-cvd or catalyst or wire or hotwire) | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 12:08 |
| S124 | 199 | S122 and (cat-cvd or catalyst or catalytic (CVD or chemical vapor deposition) or wire or hotwire) | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 12:09 |
| S125 | 9 | S122 and (cat-cvd or catalyst or catalytic) (CVD or chemical vapor deposition) or hot wire or hotwire) | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 12:10 |

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| S126 | 32 | S119 and (cat-cvd or (catalyst or catalytic) (CVD or chemical vapor deposition) or hot wire or hotwire) | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 12:10 |
| S127 | 18241 | S118 and (siN or silicon nitride or "si.sub.3n.sub.4") same ("h.sub.2" or hydrogen) | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 12:13 |
| S128 | 189 | S127 and (cat-cvd or (catalyst or catalytic) (CVD or chemical vapor deposition) or hot wire or hotwire) | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 12:13 |
| S129 | 69 | S128 and (hydrogen or "h.sub.2" or "nh.sub.3" or ammonia) with (treat\$6 or post-treat\$6 or anneal\$4) | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 12:13 |
| S130 | 4 | ("2002/0086557").URPN. | USPAT | ADJ | ON | 2011/03/30 12:19 |
| S131 | 16 | "6069094" | USPAT | ADJ | ON | 2011/03/30 12:20 |
| S132 | 17 | "6069094" | US-PGPUB; USPAT | ADJ | ON | 2011/03/30 12:20 |
| S133 | 6 | S132 and (hydrogen or "h.sub.2" or "nh.sub.3" or ammonia) with (treat\$6 or post-treat\$6 or anneal\$4) | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 12:20 |
| S134 | 503 | (siN or silicon nitride or "si.sub.3n.sub.4") same (remov \$6) adj3 (cl or chlorine or halide or halogen or hydrogen) | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2011/03/30 12:33 |
| S135 | 216 | (siN or silicon nitride or "si.sub.3n.sub.4") with (remov \$6) adj3 (cl or chlorine or halide or halogen or hydrogen) | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2011/03/30 12:33 |
| S136 | 188 | (siN or silicon nitride or "si.sub.3n.sub.4") with (remov \$6) adj3 ("h.sub.2" or hydrogen) | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2011/03/30 12:36 |
| S137 | 289 | (siN or silicon nitride or "si.sub.3n.sub.4") same (cat-cvd or (catalyst or catalytic) (CVD or chemical vapor deposition) or hot wire or hotwire) | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2011/03/30 12:38 |

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| S138 | 63 | (siN or silicon nitride or "si. sub.3n.sub.4") and (cat-cvd or (catalyst or catalytic) (CVD or chemical vapor deposition) or hot wire or hotwire) and (h or hydrogen) (content or impurity) | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2011/03/30 12:39 |
| S139 | 80 | "250438" | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2011/03/30 12:51 |
| S140 | 2 | "6709512".pn. | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2011/03/30 13:06 |
| S141 | 0 | Applied Physics with "66" with "No." | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2011/03/30 13:11 |
| S143 | 76 | Applied Physics with "66" and catalyt\$4 | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2011/03/30 13:12 |
| S144 | 19 | 8-250438 | US-PGPUB; USPAT; EPO; DERWENT | ADJ | ON | 2011/03/30 13:20 |
| S145 | 1 | 10/593444 | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 15:11 |
| S146 | 89 | (HCD or "Si.sub.2cl.sub.6" or hexachlorodisilane) and (cataly\$6 (CVD or chemical vapor) or Cat-CVD or hot- wire) | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 15:22 |
| S147 | 164 | (disilane) and (cataly\$6 (CVD or chemical vapor) or Cat-CVD or hot-wire) | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 15:25 |
| S148 | 25 | (disilane) same (cataly\$6 (CVD or chemical vapor) or Cat-CVD or hot-wire) | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 15:25 |
| S149 | 741 | (silane or "sih.sub.4") and (cataly\$6 (CVD or chemical vapor) or Cat-CVD or hot- wire) | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 15:29 |
| S150 | 636 | (silane or "sih.sub.4") and (cataly\$6 (CVD or chemical vapor) or Cat-CVD or hot- wire) and (impur\$6 or hydrogen) | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 15:30 |
| S151 | 69 | (silane or "sih.sub.4") and (cataly\$6 (CVD or chemical vapor) or Cat-CVD or hot- wire) and (impur\$6 or hydrogen) (content or level) | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 15:30 |

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| S152 | 4227 | (silane or "sih.sub.4") and (impur\$6 or hydrogen) (content or level) | US-PGPUB; USPAT; EPO; JPO | ADJ | ON | 2011/03/30 16:21 |
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EAST Search History (Interference)

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